Homework # 2. See problems on the next page. Use the information below.

Assume design is being done with the 0.6 um process cited below and assume the following information:

$$I_{ds} = \begin{cases} 0 & V_{gs} < V_t & \text{cutoff} \\ \beta \left(V_{gs} - V_t - \frac{V_{ds}}{2} \right) V_{ds} & V_{ds} < V_{dsat} & \text{linear} \\ \frac{\beta}{2} \left(V_{gs} - V_t \right)^2 & V_{ds} > V_{dsat} & \text{saturation} \end{cases}$$

- Parameters from a 0.6 µm process
 - From AMI Semiconductor
 - t_{ox} = 100 Å
 - μ = 350 cm²/V*s (mobility for n type mosfets)
 - $V_t = 0.7$ V for n-mosfets and 0.7V for p-mosfets

$$\beta = \mu C_{ox} \frac{W}{L} = (350) \left(\frac{3.9 \times 8.85 \cdot 10^{-14}}{100 \cdot 10^{-8}} \right) \left(\frac{W}{L} \right) = 120 \frac{W}{L} \mu A/V^2$$

